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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

INTERVIEW SUMMARY

Applicant(s): Mahajani et al. Application No.: 10/079472

Filed: 2/19/2002

Title: Gate Dielectric Structures for

Integrated Circuits and Methods for Making and Using Such Gate Dielectric Structures

Attorney Docket No.: MA-068

Group Art Unit: 2814

Examiner: Thao X. Le

To the Commisioner:

Examiner Thao X. Le, Supervisor Wael Fahmy, and Agent for Applicants Pamela J. Squyres participated in a telephone interview on April 3, 2003.

All rejected claims were discussed relative to the Luoh et al. reference. US Publication No. 2003/0017670.

Substance of interview: Applicants' representative explained how claim 1 and dependents, and all claims including SONOS limitations, distinguish over Fig. 2 of Luoh et al., and why the 102 and 103 rejections should be withdrawn. Also noted that 103 rejections of March 6 office action do not establish motivation to modify one ambine ECEIVED

Possible claim amendments were discussed.

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Pamela J. Squyres
Agent for Applicants

Reg. No. 52,246

I hereby certify that this paper is being transmitted by facsimile to the U.S. Patent and Trademark Office on the date shown below.

Pamela J. Squyres

Date of Transmission